

用於 CMP Slurry 及光阻劑分子間物理現象的探討



- 技術原理：全新設計應用 Low Field NMR 技術，利用 T1/T2 與 Rno，快速分析粒子分子間濕潤/親水、聚集、懸浮、分散/均勻、沉降、穩定等界面的物理特性
- 簡易，快速分析(幾十秒到幾分鐘)；適合原料進場檢驗；生產製程即時檢驗；成品 QC 確認；使用端品質再確認檢測等及研發等應用
- RelaxFlow 適合連續分析 (inline stop-flow, auto- measurement)

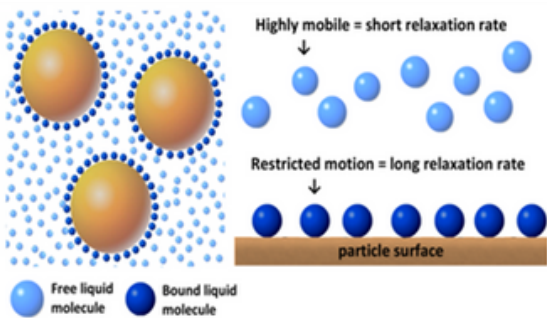
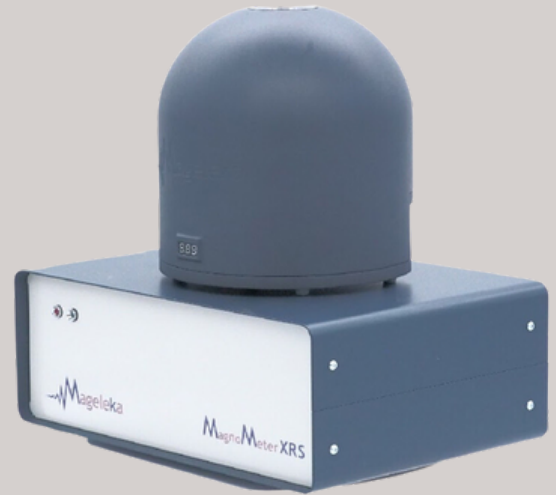
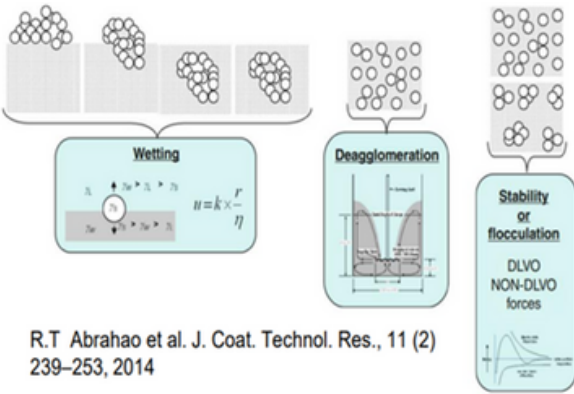
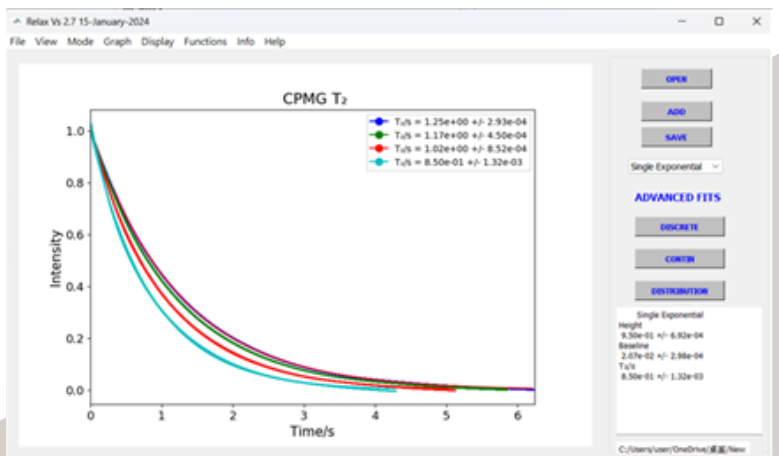
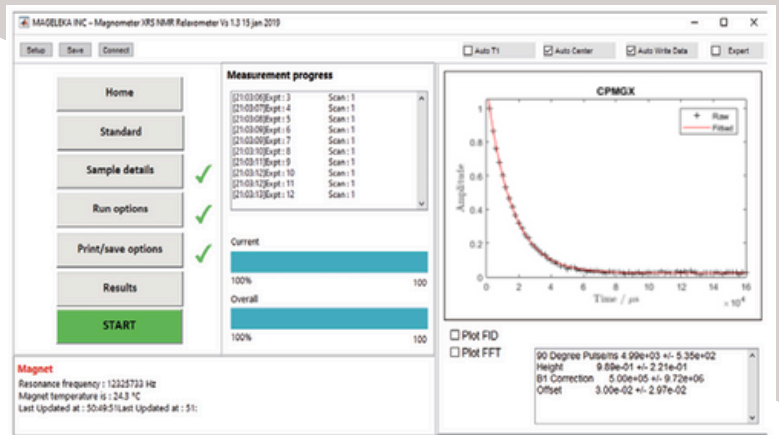


Figure 1: Schematic of bound and free liquid molecules and their relationships with NMR relaxation time. The relaxation rate is the inverse of the relaxation time.



R.T. Abrahao et al. J. Coat. Technol. Res., 11 (2) 239-253, 2014



半導體產業應用：

- CMP 磨料顆粒現象探討
- CMP 懸浮液穩定性
- CMP 漿料消耗與補充管理
- CMP 後/光阻劑清洗效率與殘留物檢測
- 光阻劑成分比例 QC/ 粘度與流動性評估
- 光阻劑老化和穩定性分析
- 光阻劑交聯程度檢測
- 光阻劑批次一致性確認

